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AMENDMENTS TO THE CLAIMS:

The following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

LISTING OF CLAIMS:

1 and 2 (Cancelled).

- 3. (Previously presented) A photosensitive resin composition according to claim 11, wherein said diamine is a diaminopolysiloxane.
- 4. (Previously presented) A photosensitive resin composition according to claim 11, wherein said transmittance is in a range of 40%-68%.
 - 5-9. (Cancelled).
- 10. (Currently amended) A photosensitive resin composition which eemprises consists essentially of (1) a polyimide precursor produced using (a) an oxydiphthalic acid or acid anhydride thereof as a reactant for forming the polyimide precursor, and (b) at least one diamine selected from the group consisting of diaminodiphenyl ether, diaminodiphenyl sulfone, metaphenylene diamine, p-phenylenediamine, p-xylylenediamine, diaminonaphthalene, dimethylbenzidine, dimethoxylbenzidine, diaminodiphenylmethane, diaminodiphenylsulfide, benzophenonediamine, bis{(aminophenoxy) phenyl}sulfone, hexafluorobis(aminophenyl)propane, bis{(aminophenoxy)phenyl}propane, dimethyldiaminophenyl-methane, tetramethyl-diaminodiphenylmethane, bis{(aminophenoxy)phenyl} sulfone, bis{(aminophenyl)propane and

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diaminopolysiloxane, (2) an addition-polymerizable compound, and (3) a photoinitiator, and which is adapted to be exposed and developed using an i-line stepper which uses monochromatic light, the polyimide precursor being such that a 20 µm thick film thereof has a transmittance, at 365nm, of at least 40%.

- 11. (Original) A photosensitive resin composition according to claim 10, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.
- 12. (Original) A photosensitive resin composition according to claim 11, wherein said diamine is a diaminodiphenyl ether.
- 13. (Original) A photosensitive resin composition according to claim 10, wherein said diamine is a diaminodiphenyl ether.
 - 14-16. (Cancelled).
- 17. (Previously presented) A photosensitive resin according to claim 13, wherein the diamine is selected from the group consisting of 4,4'-diaminodiphenyl ether, 2,4'-diaminodiphenyl ether, 3,4'-diaminodiphenyl ether and 3,3'-diaminodiphenyl ether.
 - 18. (Cancelled).
- 19. (Currently amended) A photosensitive resin composition according to claim 10, wherein said at least one diamine is selected from the group consisting of

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4, 4'-diaminodiphenyl ether, 2, 4'-diaminodiphenyl ether, 3, 4'-diaminodyphenyl ether, 3, 3'-diaminodiphenyl ether, 4, 4'-diaminodiphenyl sulfone, 3, 3'-diaminodiphenyl sulfone and metaphenylenediamine.

- 20. (Previously presented) A photosensitive resin composition according to claim 19, wherein said at least one diamine is selected from the group consisting of 3, 4'-diaminodiphenyl ether, 3, 3'-diaminodiphenyl sulfone, 4, 4'-diaminodiphenyl sulfone and methaphenylenediamine.
- 21. (Previously presented) A photosensitive resin composition according to claim 10, wherein the at least one diamine includes a diaminopolysiloxane represented by the formula (III):

(III):

$$H_2N - R^5 \left(\begin{array}{c} R^7 \\ Si - O \\ R^8 \end{array}\right) \left(\begin{array}{c} R^7 \\ Si - R^6 - NH_2 \end{array}\right)$$
 (III)

wherein R⁵ and R⁶ each represent a divalent hydrocarbon group; R⁷ and R⁸ each represent a monovalent hydrocarbon group; each of R⁵, R⁶, R⁷ and R° may be the same or different; and t represents an integer of 1 to 5.

22. (Previously presented) A photosensitive resin composition according to claim 21, wherein said divalent hydrocarbon group has 1 to 3 carbon atoms, and said monovalent hydrocarbon group has 1 to 3 carbon atoms.

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- 23. (Previously presented) A photosensitive resin composition which comprises (1) a polyimide precursor produced using (a) an oxydiphthalic acid or acid anhydride thereof as a reactant for forming the polyimide precursor, and (b) at least one diamine including a hydroxyl group-containing diamine, (2) an addition-polymerizable compound, and (3) a photoinitiator, and which is adapted to be exposed and developed using an i-line stepper which uses monochromatic light, the polyimide precursor being such that a 20 μm thick film thereof has a transmittance, at 365 nm, of at least 40%.
- 24. (New) A photosensitive resin composition according to claim 10, wherein said polyimide precursor is a condensation product of said oxydiphthalic acid or acid anhydride thereof and said at least one diamine.
- 25. (New) A photosensitive resin composition according to claim 10, wherein said at least one diamine is selected from the group consisting of diaminodiphenyl sulfone, metaphenylene diamine, p-phenylenediamine, p-xylylenediamine, diaminonaphthalene, dimethylbenzidine, dimethoxylbenzidine, diaminodiphenylmethane, diaminodiphenylsulfide, benzophenonediamine, bis{(aminophenoxy) phenyl}sulfone, hexafluoro-bis(aminophenyl)propane, bis{(aminophenoxy)phenyl}propane, dimethyl-diaminophenyl-methane, tetramethyl-diaminodiphenylmethane, bis{(aminophenoxy)phenyl} sulfone, bis{(aminophenyl)propane and diaminopolysiloxane.